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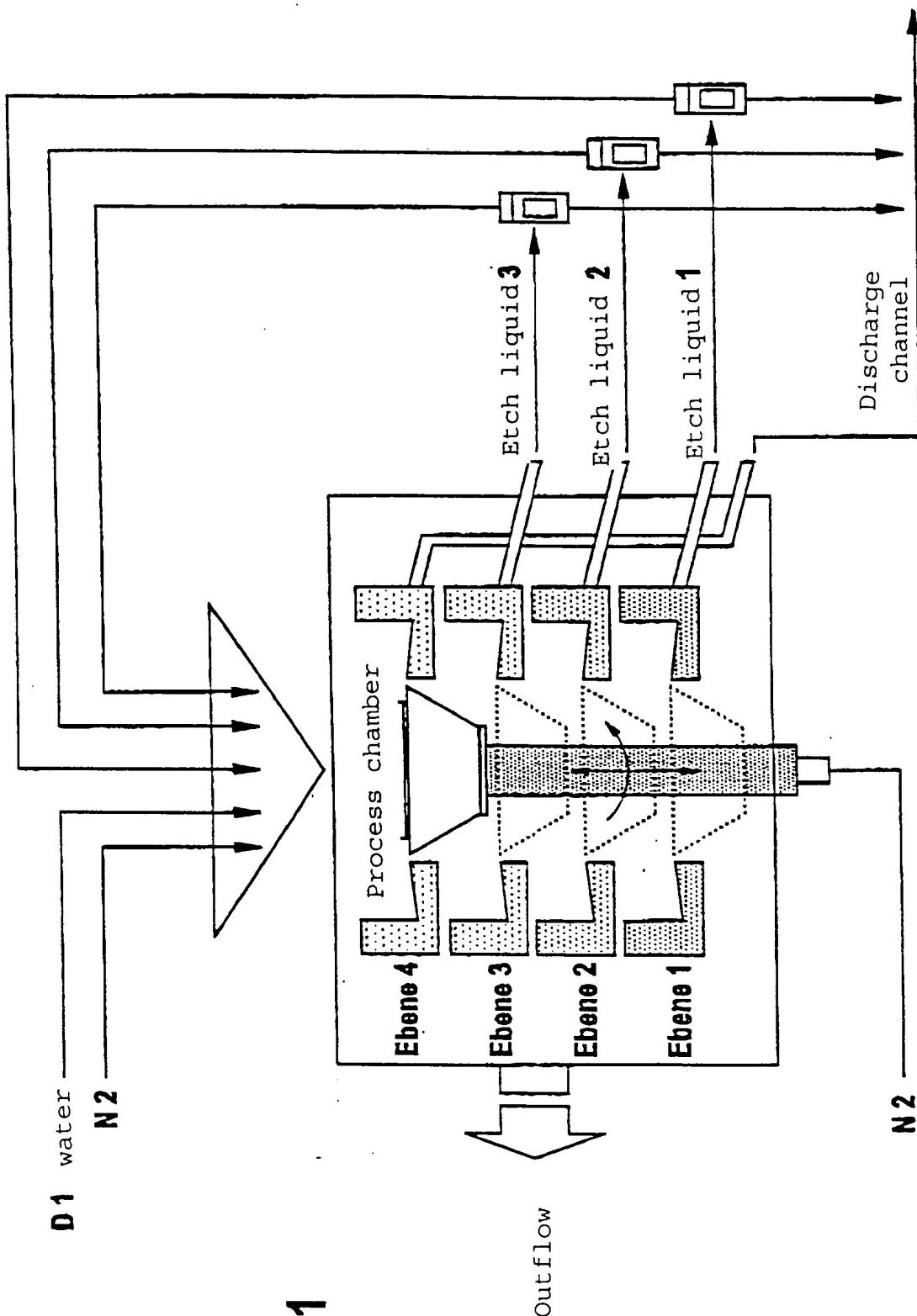


Fig. 1

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Heading = Wafer profile after etching with spin etch F
in a spin etcher

Diagram 1

Vertical measurement values

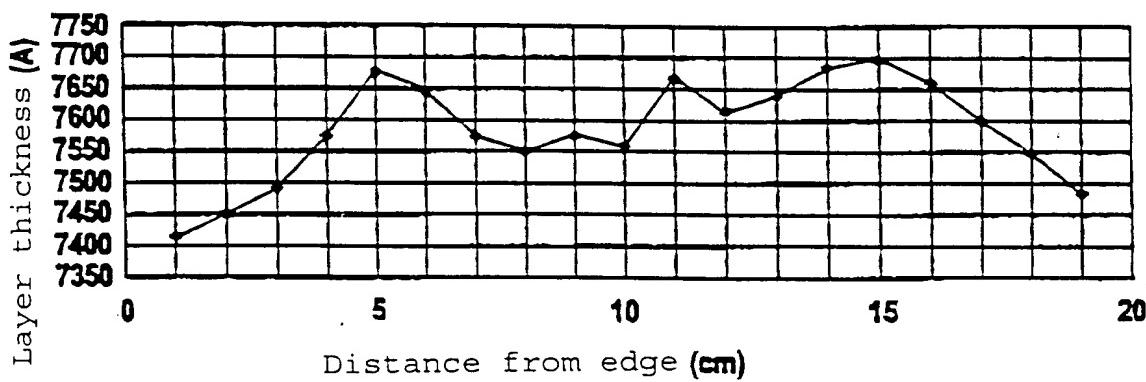
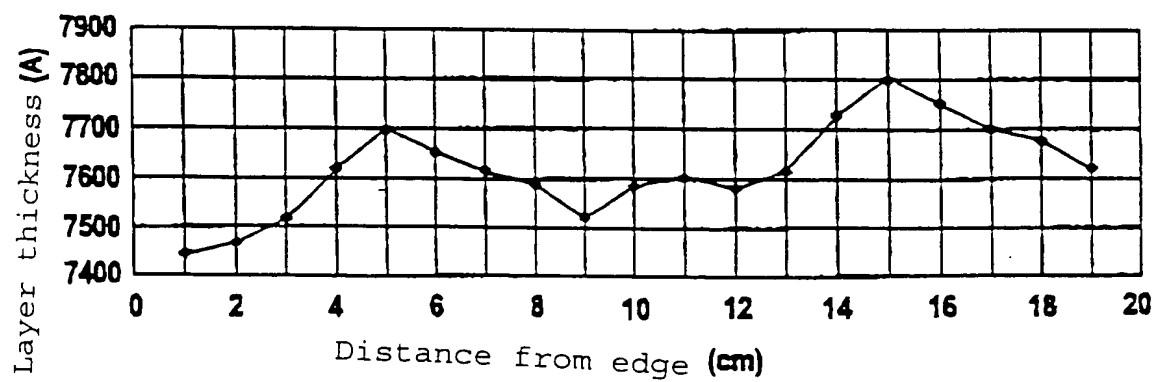


Diagram 2

Horizontal measurement values



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Wafer profile after etching with ethylene
glycol / HF (15%) in a spin etcher

Diagram 3

Vertical measurement values

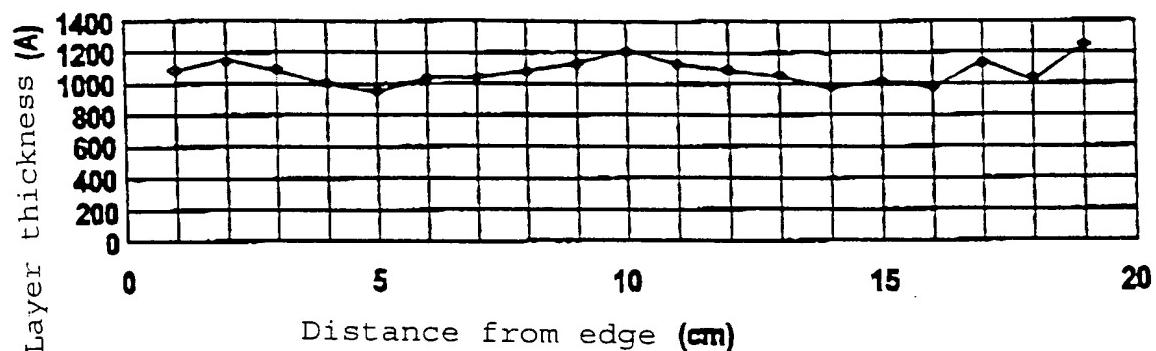
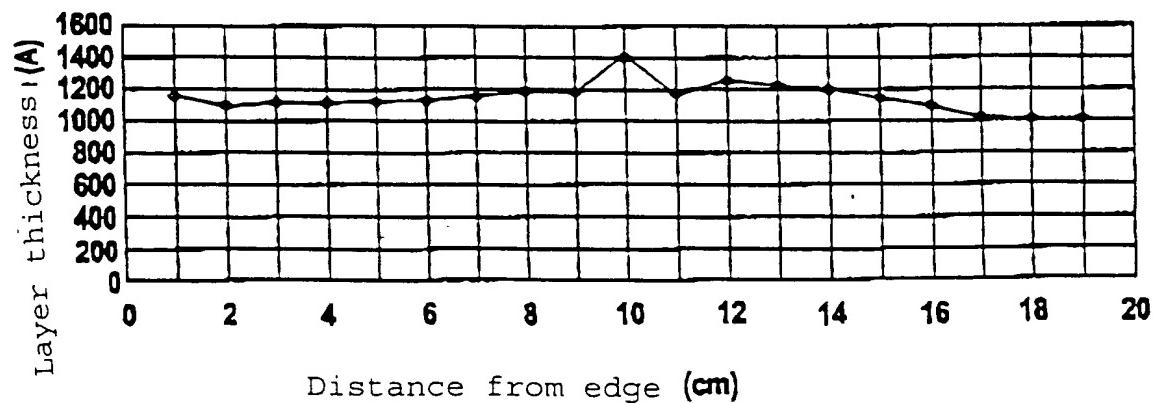


Diagram 4

Horizontal measurement values



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Wafer profile after etching with ethylene
glycol / glycerol / HF (15%) in a spin etcher

Diagram 5

Vertical measurement values

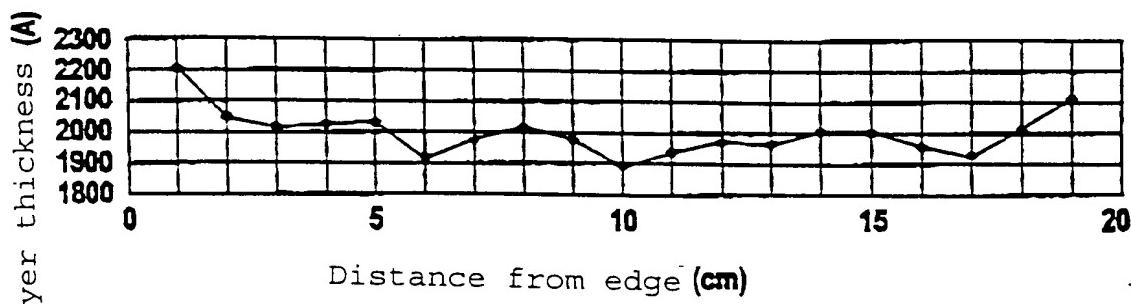


Diagram 6

Horizontal measurement values

